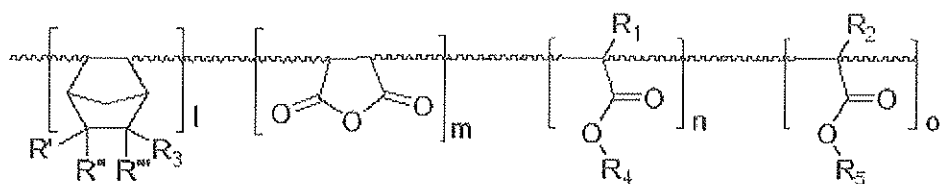


ADDITIVE FOR RESIST AND RESIST COMPOSITION COMPRISING SAME

ABSTRACT OF THE DISCLOSURE

5 Provided are an additive for resist represented by
the following formula (1), and a resist composition
containing the additive. The additive according to the
present invention can suppress leaching caused by water
during an immersion lithographic process by increasing
10 hydrophobicity of the surface of the resist film in the
exposure at the time of applying the additive to a resist
composition, and can form a fine resist pattern having
excellent sensitivity and resolution at the time of
applying the additive to a resist composition.

15 [Chemical Formula 1]



wherein the substituents respectively have the same
meanings as defined above.